



National Aeronautics and
Space Administration



Criticality of Low-Energy Protons in Single-Event Effects Testing of Highly-Scaled Technologies

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Department of Energy's National Nuclear Security Administration under Contract DE-AC04-94AL85000.**

Acronyms



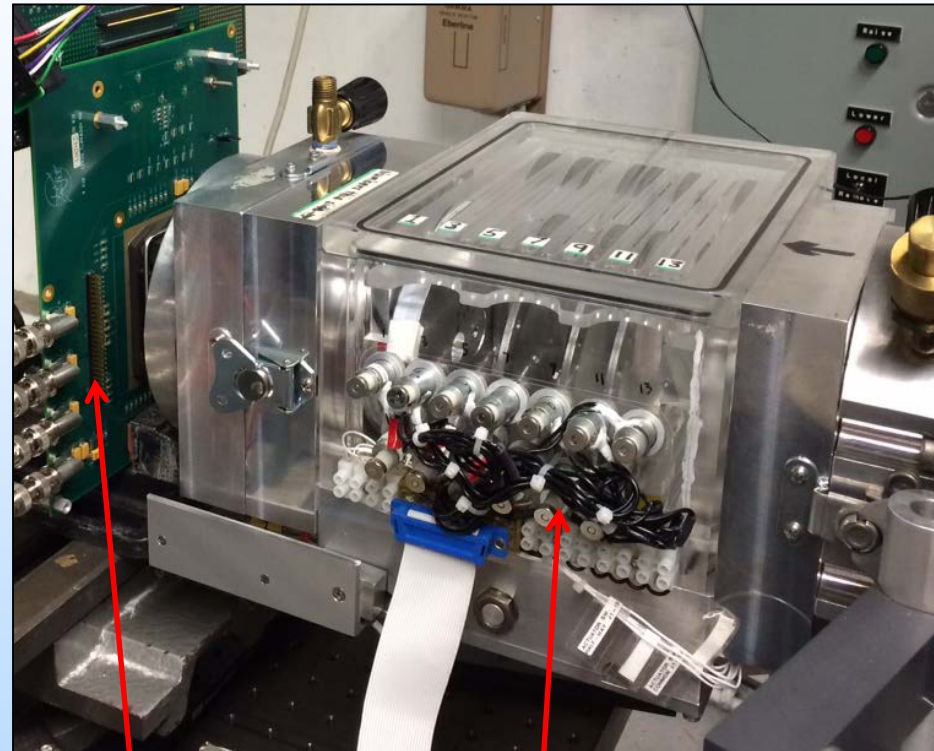
- **CMOS:** complementary metal oxide semiconductor
- **CNL:** Crocker Nuclear Laboratory
- **CSDA:** continuous slowing down approximation
- **DBU:** double-bit upset
- **DUT:** device under test
- **IBM YKT:** Yorktown Heights, NY
- **ICRU:** International Commission on Radiation Units & Measurements
- **IEEE:** Institute of Electrical and Electronics Engineers
- **IUCF:** Indiana University Cyclotron Facility
- **LBNL:** Lawrence Berkeley National Laboratory
- **LEP:** low-energy proton
- **MCU:** multi-cell upset (errors not necessarily in the same data word)
 - Different from multi-bit upset (MBU)
- **NIST:** National Institute of Standards and Technology
 - ASTAR and PSTAR are NIST tools, not acronyms
- **NPTC:** Northeast Proton Therapy Center
- **SBU:** single-bit upset
- **SEEM:** secondary electron emission monitor
- **SEU:** single-event upset
- **SOI:** silicon on insulator
- **SRAM:** static random access memory
- **SRIM:** Stopping and Range of Ions in Matter (software program)
- **TNS:** Transactions on Nuclear Science
- **TRIUMF:** not an acronym – formerly the Tri-University Meson Facility, Vancouver, Canada
- **UC Davis:** University of California at Davis

Outline



- **Introduction**
 - Low-energy protons (LEPs)
 - Test facility setup
- **Protons vs. alphas**
- **DUT is 32 nm SOI CMOS 128 Mb SRAM**
 - Heavy ion data baseline
 - DUT is in a flip-chip package
- **SBU and MCU SRAM data**
- **Die thickness reverse engineering with SRIM**
- **Summary**

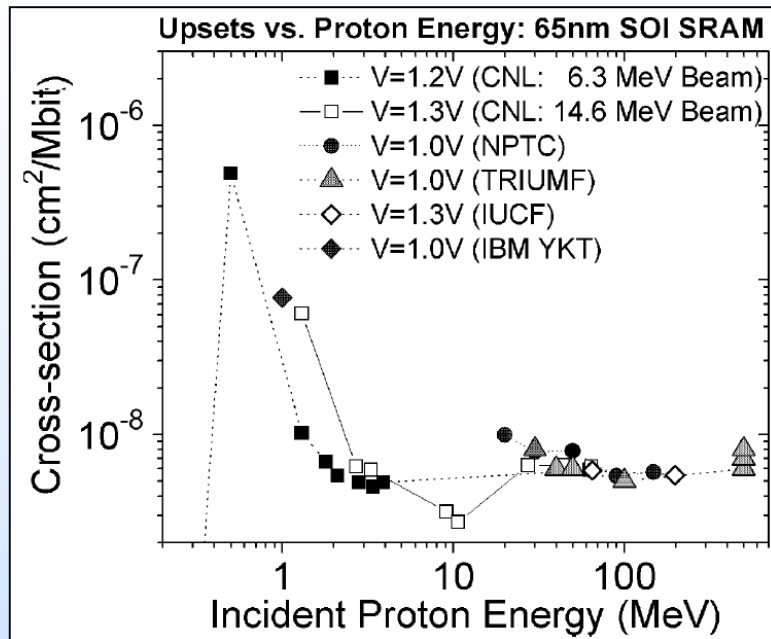
UC Davis CNL Test Setup



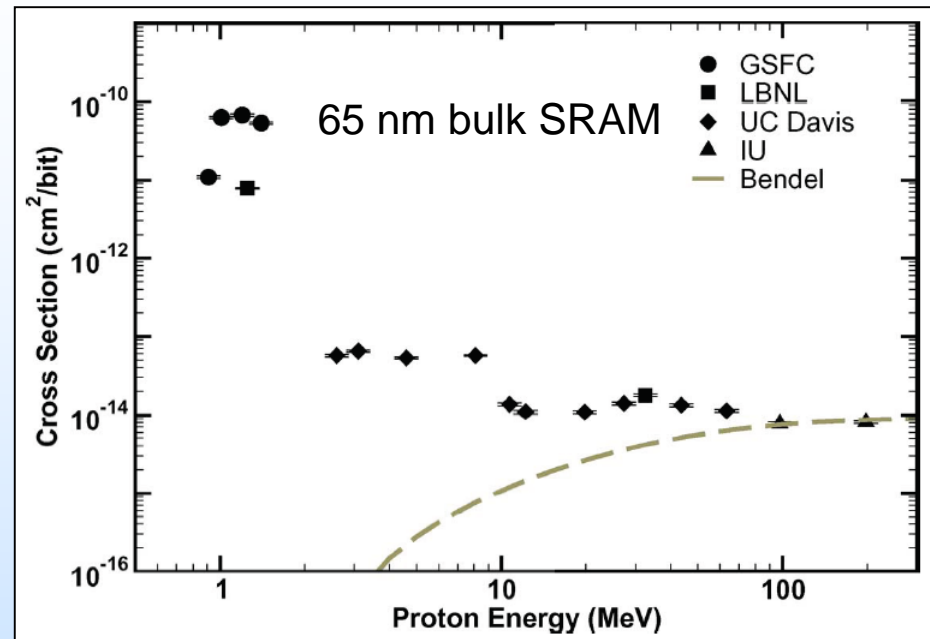
Test board

User-Controlled Degradation Foil Chamber

Early Low-Energy Proton Data



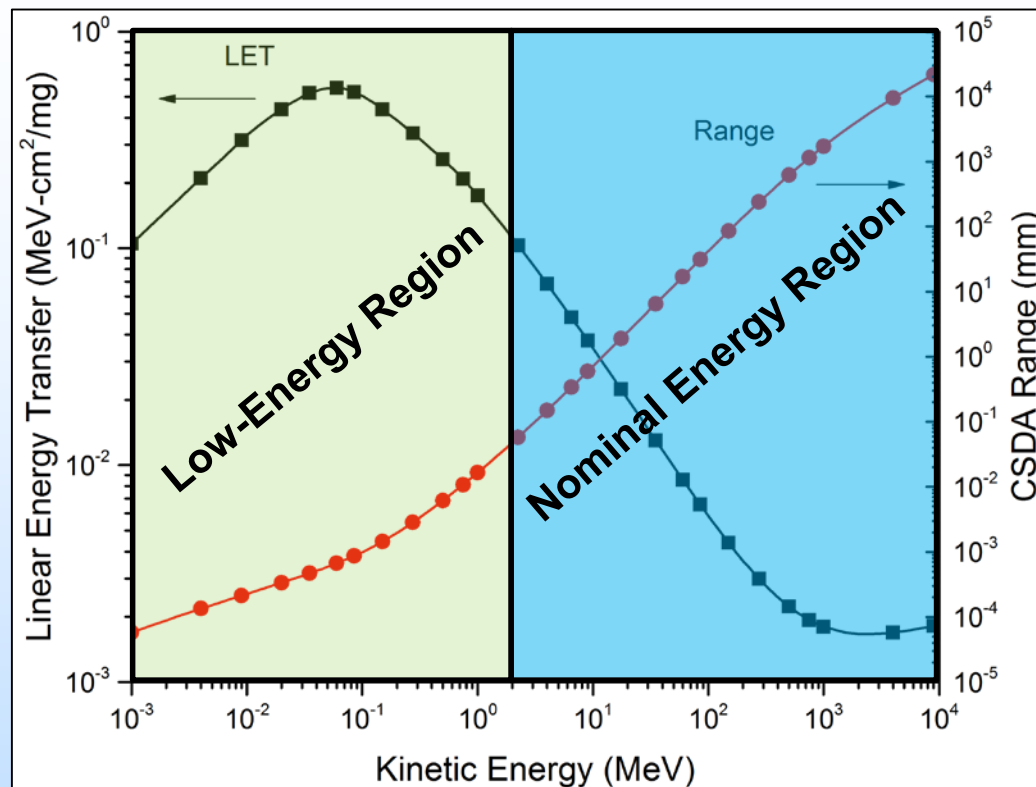
D. F. Heidel et al., IEEE TNS, vol. 6, 2008.



B. D. Sierawski et al., IEEE TNS, vol. 6, 2009.

- Cross sections are plotted as a function of incident proton energy – inversely proportional to degrader thickness.
 - Several implications: changes to the energy distribution shape, flux depletion near end-of-range, etc.
 - Can plot data as a function of degrader thickness.
- How do we know the mean energy and standard deviation?

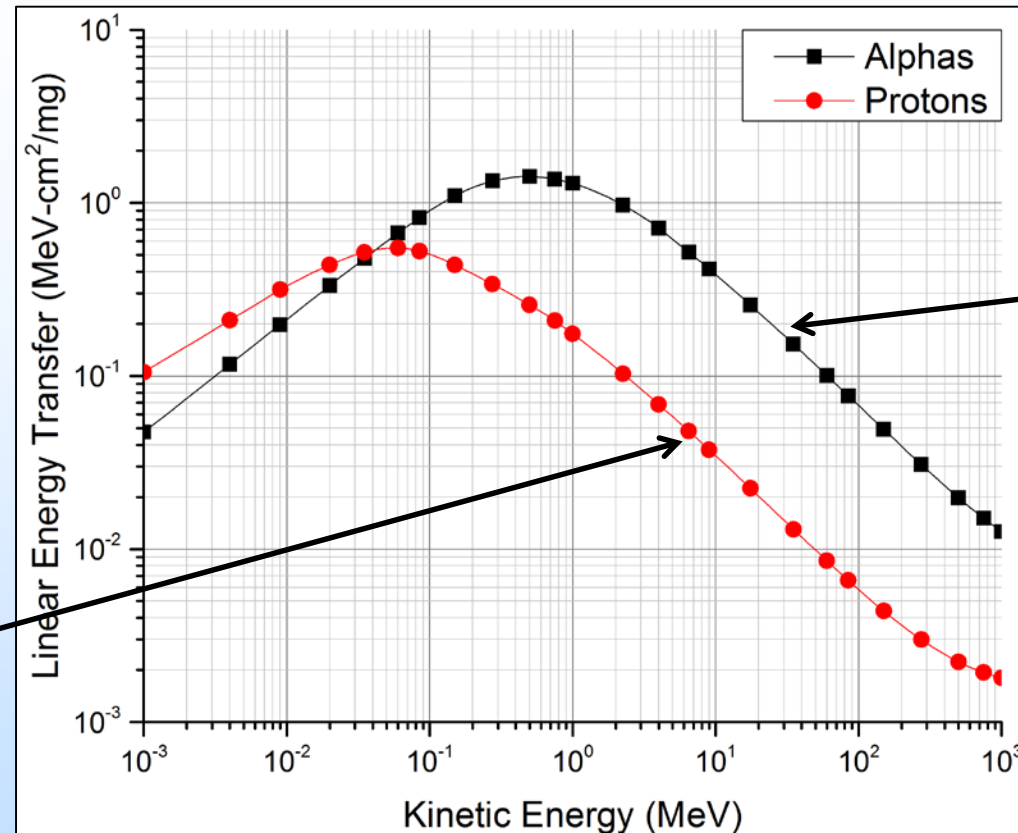
The Problem with LEPs – Range & dE/dx



NIST PSTAR tool (ICRU Report 49, 1993).

- Greatest effect in the shortest distance
- Short range in region of interest implies flux depletion
- Cross sections tend to be uncorrected for flux loss and plotted as a function of known quantities (e.g., degrader thickness)

The Alpha (^4He) Alternative



NIST ASTAR/PSTAR tool (ICRU Report 49, 1993).

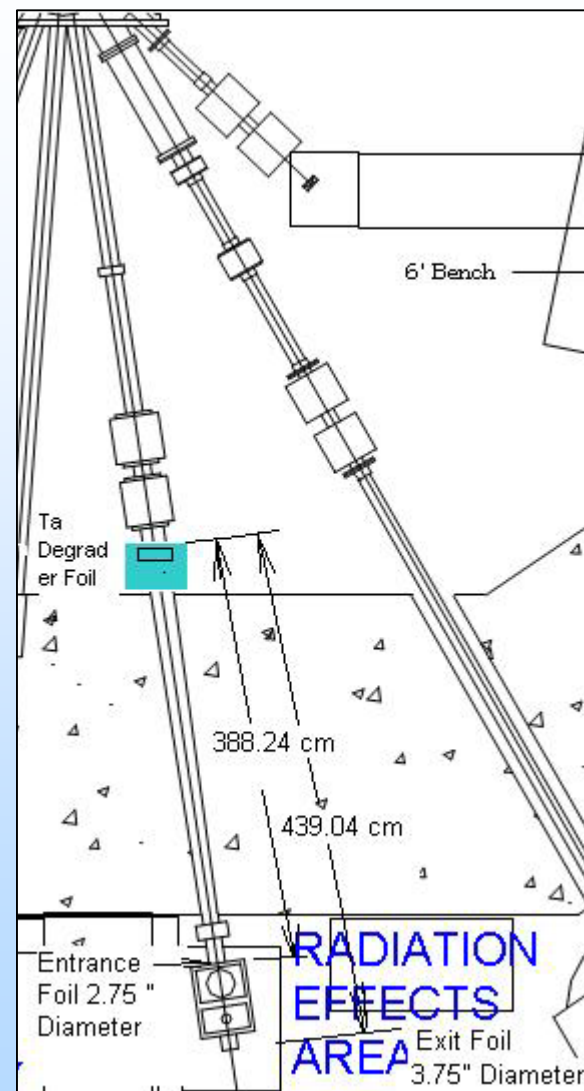
- **Hypothesis: Alpha particles can replace LEPs for direct ionization single-event effects testing.**

In the context of LEPs, mentioned as early as 2009 – B. D. Sierawski et al., including J. Pellish.

UC Davis Crocker Nuclear Laboratory

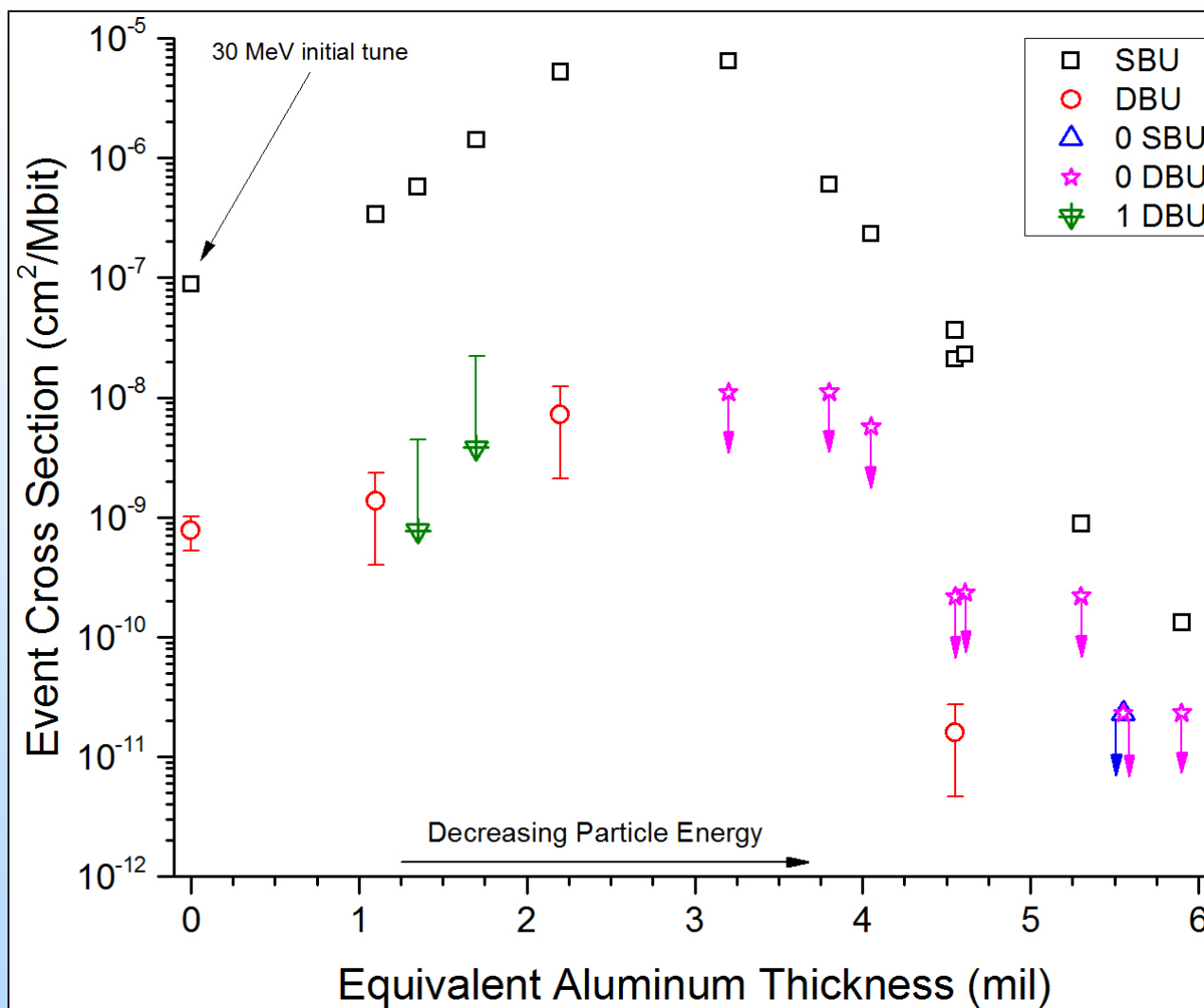
Assuming Setup In-Air (can do vacuum)

- **Beam diameter on 0.25 mil Ta foil is $\sim 5/16$ in.**
- **Defining collimator is 2.75 in with acceptance angle of 0.018 rad.**
- **Secondary electron emission monitor (SEEM) uses three 0.25 mil Al foils.**
- **User-selected degraders can be Al or Mylar.**
- **Exit window is 5 mil Kapton.**
- **Air gap is user-selected within experimental parameters.**



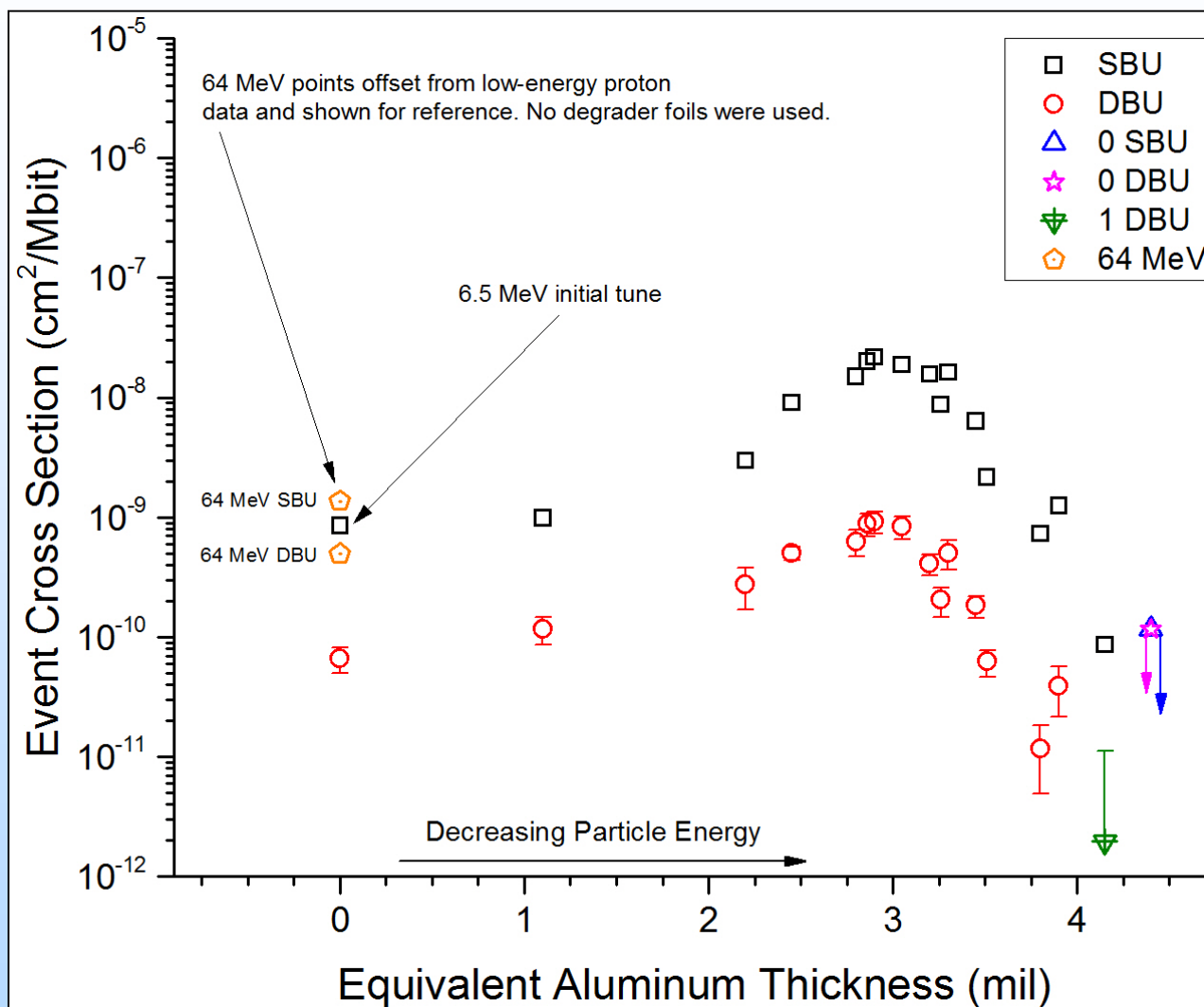
Courtesy of T. Essert and M. Van de Water (UCD/CNL).

30 MeV Alpha SEU Data 0x0000 Pattern



Error bars, if shown, are at the 90% confidence level.

6.5 MeV Proton SEU Data 0x0000 Pattern

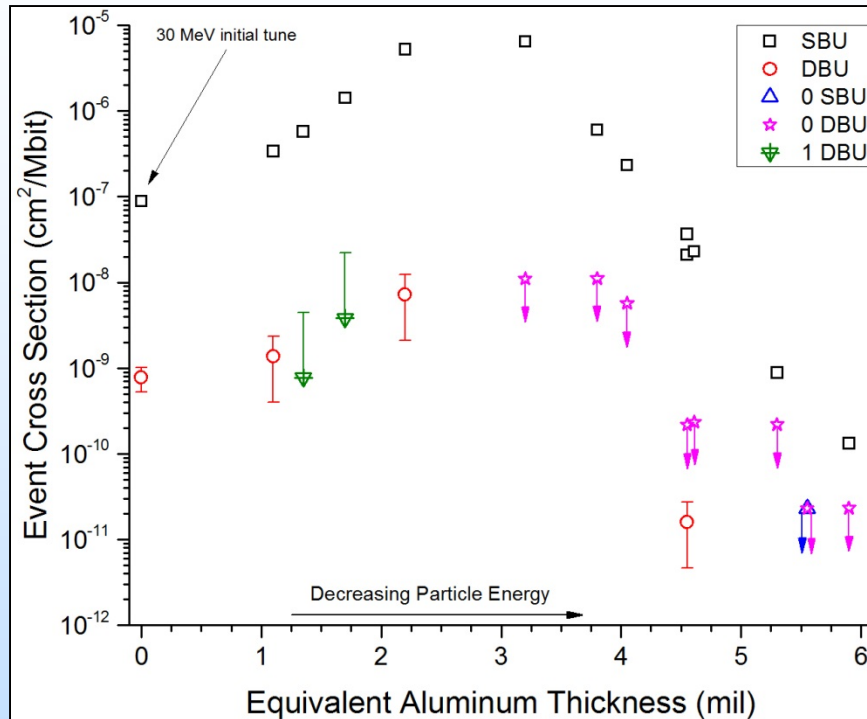


Error bars, if shown, are at the 90% confidence level.

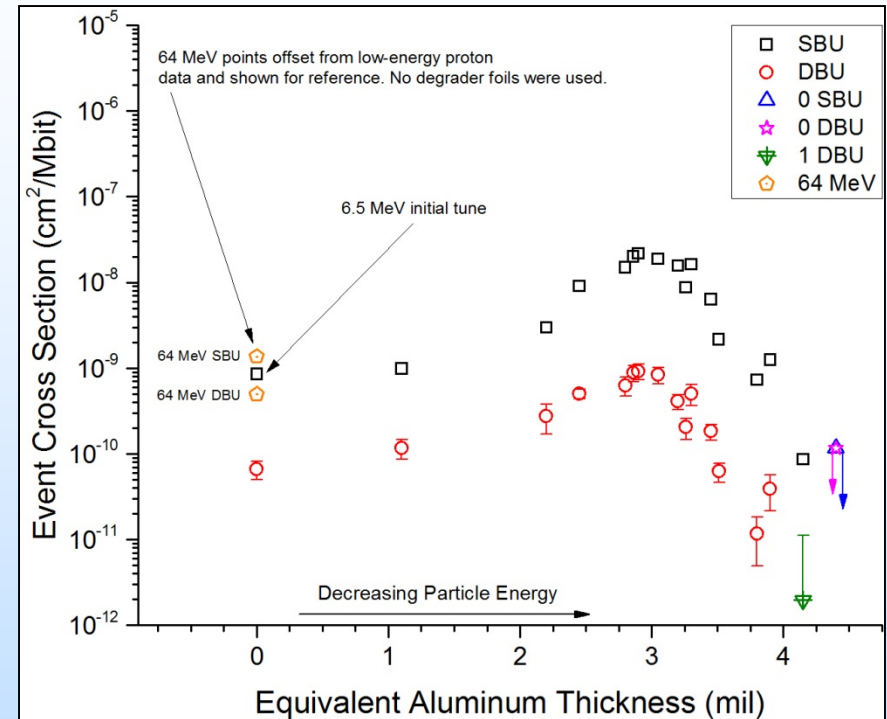
Data Comparison – Side-by-Side



Alpha

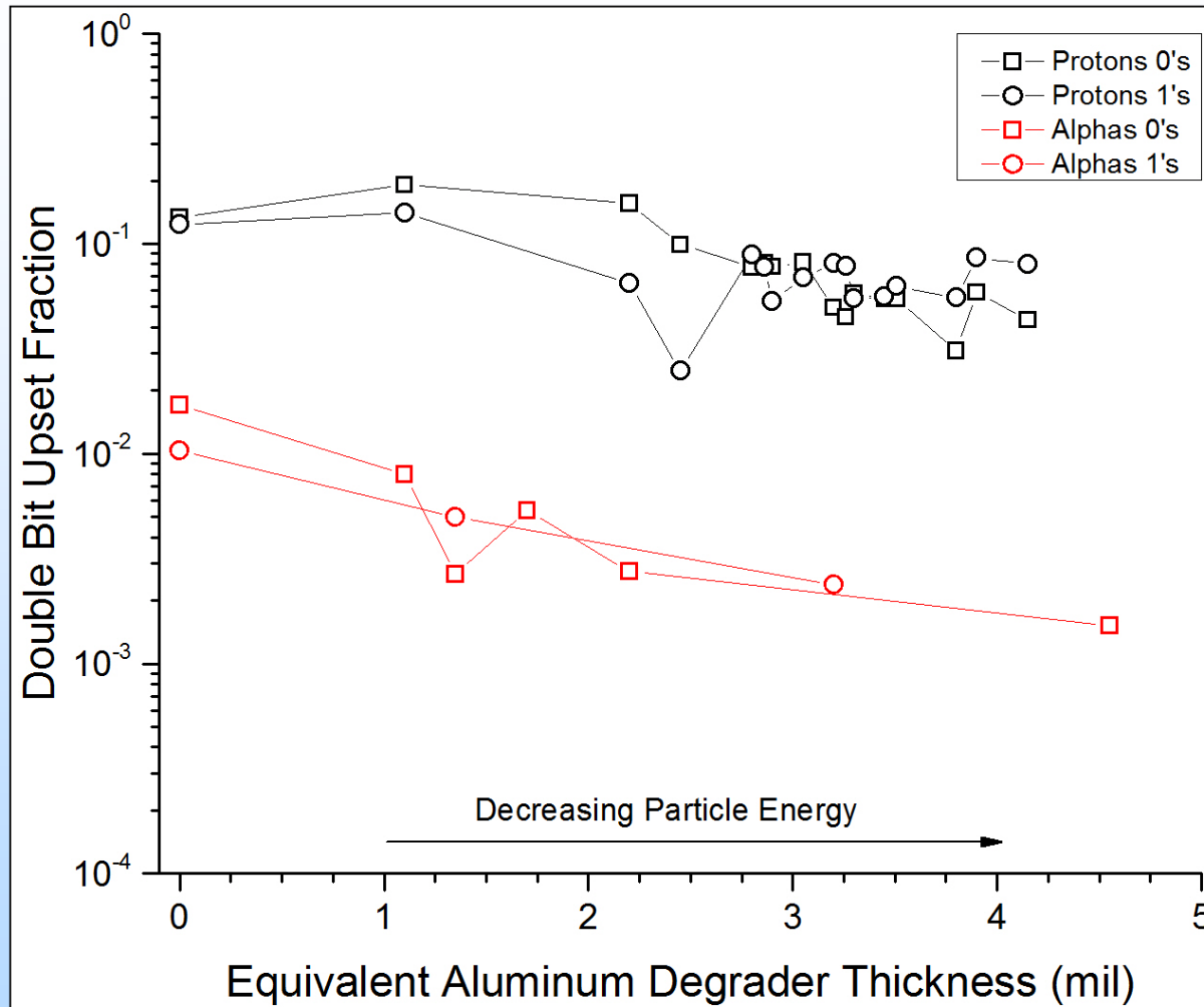


Proton



- On the low-energy side of the Bragg peak, the cross sections are similar, but the type of events are not.
- One of the key features is the separation between SBUs and DBUs.

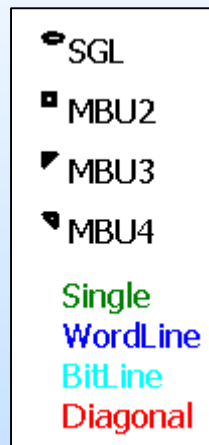
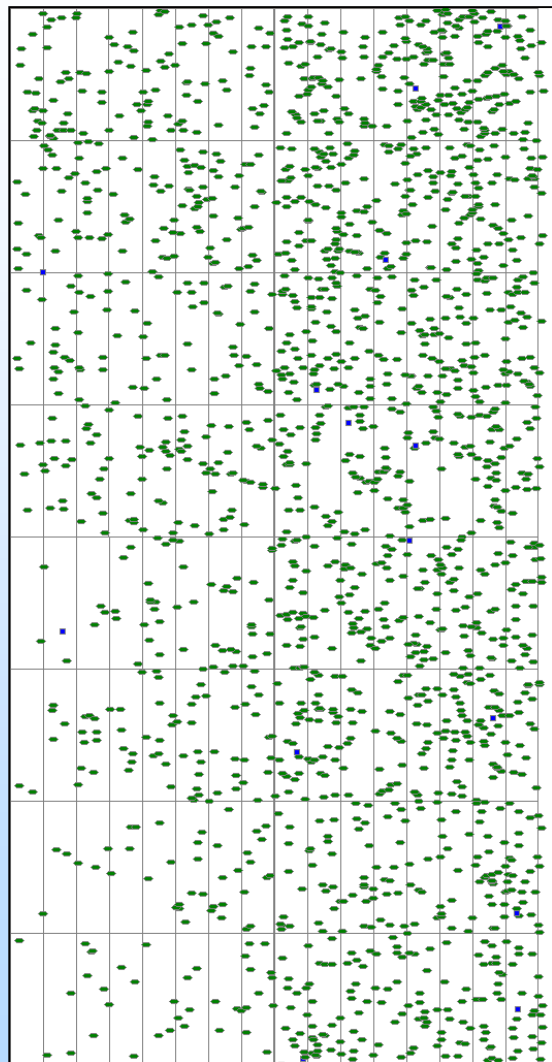
Alpha & Proton DBU Fraction



Shows both 0x0000 and 0xFFFF data patterns.

Physical Failure Maps – Alphas

0x0000 Pattern

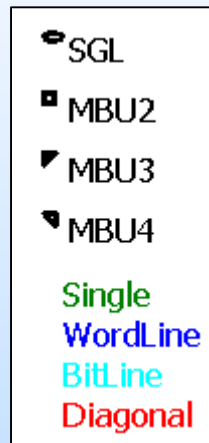
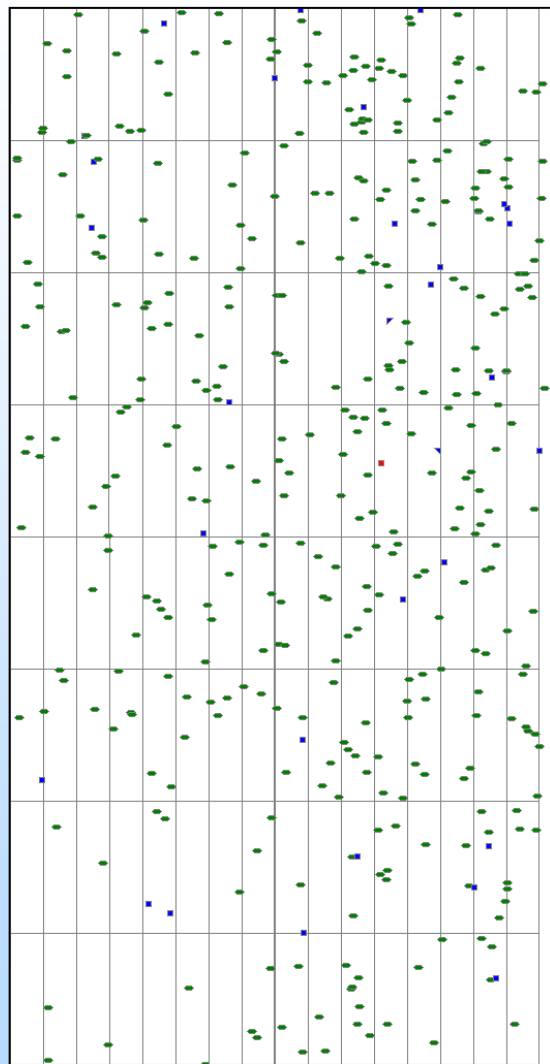


In legend – MBU = MCU

- 30 MeV primary
 - No user degrader
 - Actual alpha energy below primary tune
- Only 14 total MCUs
 - All DBUs
 - 4 on left, 10 on right
- For alpha/proton comparison, remember, these plots are absolute event counts.
 - Total fluence and LET dependencies.

Physical Failure Maps – Protons

0x0000 Pattern



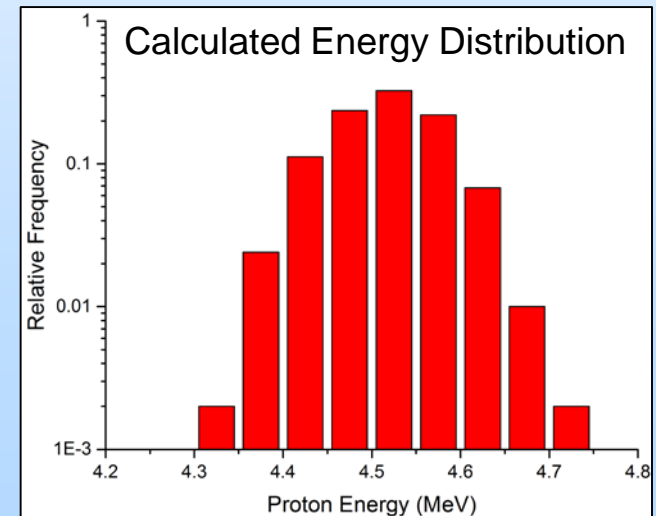
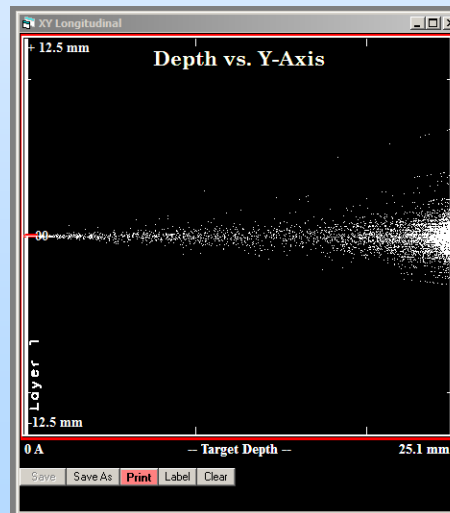
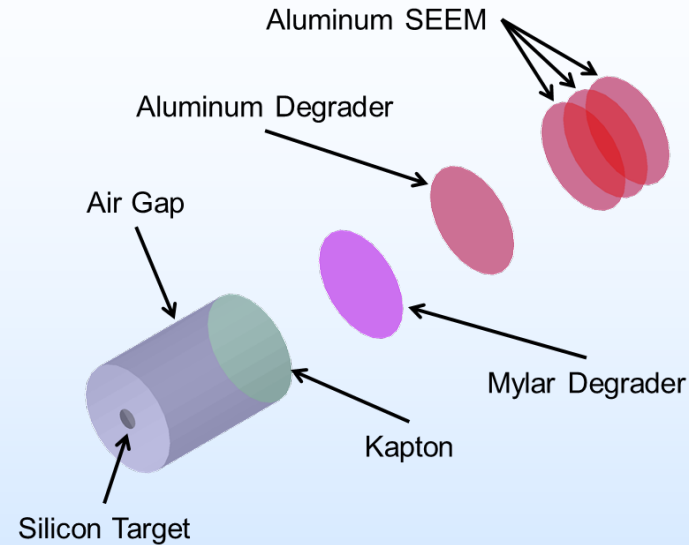
In legend – MBU = MCU

- 6.5 MeV primary
 - No user degrader
 - Actual proton energy below primary tune
- 32 total MCUs
 - 13 on left, 19 on right
- Most MCUs are word-line DBUs
 - One 3-bit MCU and one 4-bit MCU – both word line
- For alpha/proton comparison, remember, these plots are absolute event counts.
 - Total fluence and LET dependencies.

Incorporation of SRIM Simulations to Calculate Die Thickness



- Fail mapping can be used to isolate areas of interest for analysis.
- Beam stopping degrader thickness can be used to “back out” silicon die thickness.



Summary



- **Low-energy proton testing is challenging.**
- **At this point, there appears to be no suitable proxy for the observed single-event effects produced by low-energy protons.**
 - **While alpha particle and proton SBU behavior seems to be proportional to LET, the MCU behavior is not.**
 - There are subsequent implications for radiation hardness assurance.
 - **May be more room for compromise at CMOS technology nodes > 65 nm.**
- **Additional analysis techniques presented to aid data reduction efforts.**
 - **Many technologies are flip-chip (such as our SRAM DUT), and die thickness uncertainty has always been one of the larger sources of systematic error.**

Acknowledgements



- **NASA Electronic Parts and Packaging Program**
- **Defense Threat Reduction Agency**
- **National Reconnaissance Office**

Questions?